EXPRESS MAIL NO. EV336615168US

FORM PTO-1449 (REV.7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. 854063.618D1	APPLICATION NO. 10/712,211
INFORMATION DISCLOSURE STATEMENT *(Use several sheets if necessary)*		APPLICANTS Pietro Erratico et al.	
		FILING DATE November 12, 2003	GROUP ART UNIT 2815

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
JE	AA	3,969,168	07/13/76	Kuhn	156	17	
JE	AB	4,993,143	02/19/91	Sidner	29	621.1	
JE	AC	5,773,870	06/30/98	Su et al.	257	531	
JE	AD	6,001,666	12/14/99	Diem et al.	438	52	
JE	AE	6,015,761	01/18/00	Merry et al.	438	727	

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES	TRANSLATION NO
JE	AF	JP62076783	04/08/87	Japan (Abstract Only)		
JE	AG	JP62076784	04/08/87	Japan (Abstract Only)		
JE	AH	WO9417558	08/04/94	PCT		
JE	AI	0 658 927 A	06/21/95	Europe (+ Abstract)		
JE	AJ	960177-7 A	11/10/97	Sweden (+ Abstract)		
JE	AK	196 21 349 A	12/04/97	Germany (+ Abstract)		
JE	AL	1 043 770 A1	10/11/00	EP		
JE	AM	1 130 631 A1	09/05/01	EP		

OTHER PRIOR ART *(Including Author, Title, Date, Pertinent Pages, Etc.)*

JE	AN		Schubert, "Method of Making Separate Regions of Various Average Depths with One Anisotropic Etch," Research Disclosure, No. 316, Emsworth, GB, August, 1990, pp. 688-689.
JE	AO		Zou et al., "Single-Chip Fabrication of Integrated Fluid System (IFS), *IEEE Workshop on Micro Electro Mechanical Systems,* New York, NY: IEEE, 25 January 1998, pp 448-453
JE	AP		"Method of Making Separate Regions of Various Average Depths with one Anisotropic Etch," *Research Disclosure, GB, Industrial Opportunities Ltd., Havant, No. 316,* August 1990
JE	AQ		Sugiyama et al., "Micro-Diaphram Pressure Sensor," *1986 IEEE,* 8.3, 184-IEDM, pp 184-187.

EXAMINER	DATE CONSIDERED
JE Eckert	10/6/04

* EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).